

U6090-3



PATENT APPLICATION

1732  
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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of: )  
: Examiner: M. Vargot  
Stephen Y. Chou )  
: Group Art Unit: 1732  
Application No.: 10/046,594 )  
:   
Filed: October 29, 2001 )  
:   
For: IMPROVED RELEASE SURFACES, )  
PARTICULARLY FOR USE IN :  
NANOIMPRINT LITHOGRAPHY ) December 2, 2004

Mail Stop Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed on the enclosed PTO-1449. Copies of the listed documents are also enclosed. It is respectfully requested that the PTO-1449 form be initialed and returned, indicating that the cited references have been considered.

I hereby certify that this correspondence is being deposited with the United States Postal Service as first-class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on

December 2, 2004

Date of Deposit

Daniel D. Sierchio (Reg. No. 53,591

Name

Daniel D. Sierchio

Signature

December 2, 2004

Date of Signature

12/06/2004 EABUBAK1 00000106 501358 10046594

01 FC:1806 180.00 DA


FEES

The Commissioner is authorized to charge \$180.00 to Deposit Account 501358 to cover the required Information Disclosure Statement fee under 37 C.F.R. 1.17(p). Any deficiency in or overpayment of the fee may be charged or credited to this Deposit Account. A duplicate of this submission is attached for accounting purposes.

CONCLUSION

Applicants' undersigned attorney may be reached by telephone at (973) 597-2500. All correspondence should continue to be directed to our address listed below.

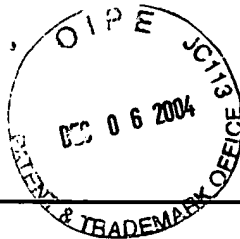
Respectfully submitted,



DANIEL D. SIERCHIO  
Attorney for Applicant

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**DOCKET ADMINISTRATOR**  
Lowenstein Sandler PC  
65 Livingston Avenue  
Roseland, NJ 07068



<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)				Docket Number (Optional) U6090-3		Application Number 10/046,594		
				Applicant(s) Stephen Y. Chou				
				Filing Date 10/29/01		Group Art Unit 1732		
<b>U.S. PATENT DOCUMENTS</b>								
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE	
<b>FOREIGN PATENT DOCUMENTS</b>								
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	TRANSLATION	
							Yes	No
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>								
		K. Pfeiffer, et al., "Reactive Polymers- a Route to Nanoimprint Lithography at Low Temperatures", June 2003, Pages 203-210						
		K. Pfeiffer, et al., "A comparison of thermally and photochemically cross-linked polymers for nanoimprinting", Microelectronic Engineering, Vol. 67-68, 2003, Pages 266-273						
		H. Schulz, et al., "Low-Temperature Wafer-Scale 'WARM' Embossing for Mix & Match with UV-Lithography", Proceedings of SPIE Vol. 4688, 2002, Pages 223-231						
		D.J. Resnick, et al., "Imprint lithography for integrated circuit fabrication", J. Vac. Sci. Technol. , B 21(6), Nov/Dec 2003, Pages 2624-2631						
		C. Gourgon, et al., "Influence of pattern density in nanoimprint lithography", J. Vac. Sci. Technol., B 21(1), Jan/Feb 2003, Pages 98-105						
		Dahl-Young Khang, et al., "Room-temperature imprint lithography by solvent vapor treatment", Applied Physics Letters, Vol. 76, No. 7, February 14, 2000, Pages 870-872						
		A. Lebib, et al., "Room-temperature and low-pressure nanoimprint lithography", Microelectronic Engineering, Vol. 61-62, 2002, Pages 371-377						
		K. Pfeiffer, et al., "Suitability of new polymer materials with adjustable glass temperature for nano-imprinting", Microelectronic Engineering, Vol. 46, 1999, Pages 431-434						
Examiner Signature				Date Considered				
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

Form PTO-A820 (also form PTO-1449)